

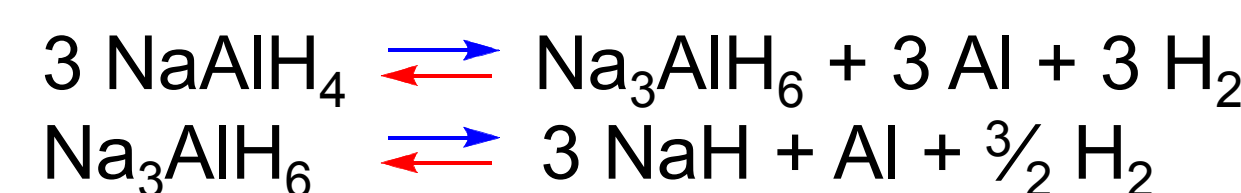
Roles of Titanium and Oxygen at the Surface in the Dehydrogenation of Titanium-Doped Sodium Aluminum Hydride

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Background and Abstract

Ti-doped NaAlH₄ (sodium alanate) is a reversible hydrogen storage material with an effective capacity of 5.6 wt%, which can be cycled below 200 °C in two steps.¹ Many studies have investigated the role of Ti in its mechanism of action, with no consensus.² The content and behavior of the surface is critical in solid-gas reactions; thus, it is essential to investigate realistic, rather than sputter-cleaned or idealized, hydride materials *in operando*. Trace amounts of highly surface-localized oxidic contaminants have typically been ignored or assumed to be passive.³ Through the use of *in situ* surface analysis during desorption, substantial changes in the speciation of oxygen atoms attached to aluminum were instead observed, indicating significant activity and a likely involvement of O in the dehydrogenation, whereas Ti, absent from the surface, can play no direct role.



Experimental Methods

Preparation and Treatment of Material

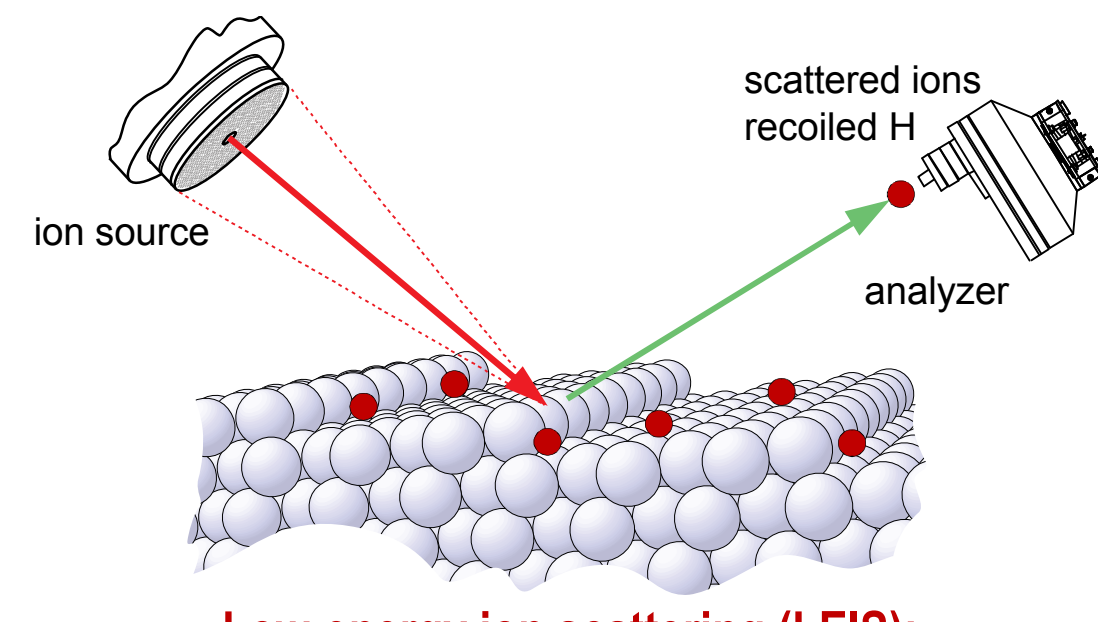
- Recrystallized NaAlH₄ in THF to remove Al and oxidized impurities
- High-energy ball-milled for 2 h with 10 mol% TiCl₃, yielding dark gray powder
- Dehydrogenated and rehydrogenated 3 times to yield realistic, cyclable material

Analysis

- Mounted powder on Pb alloy substrate for support and grounding
- Clean transfer from Ar glovebox to UHV chambers
- In operando* AP-XPS conducted at BL11.0.2, at the Advanced Light Source, LBNL
- In operando* low-energy ion scattering and *ex situ* XPS measurements at Sandia

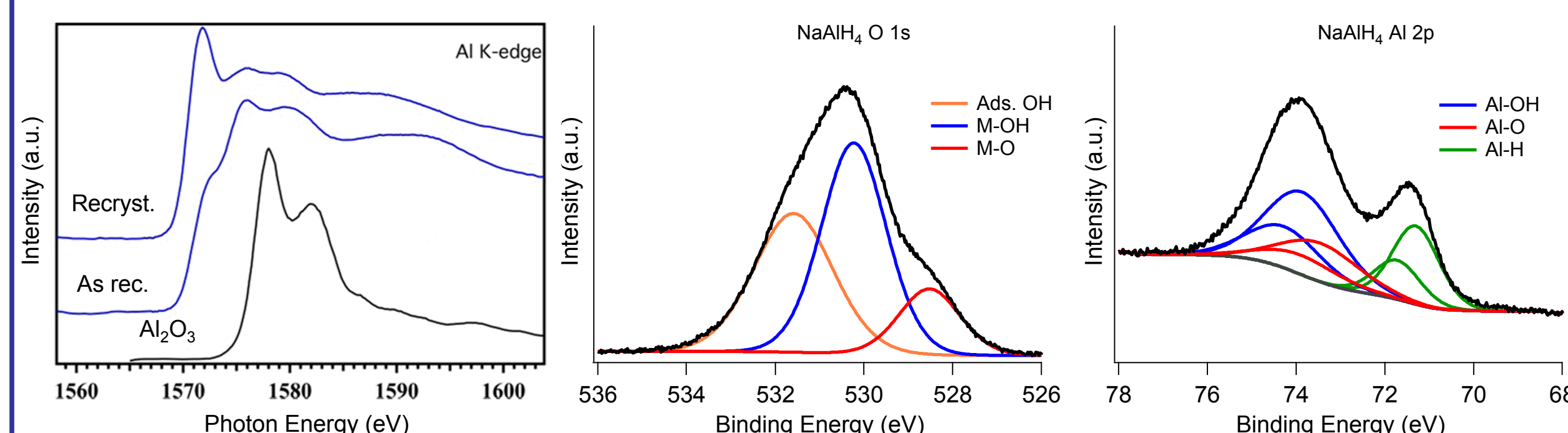


XPS Clean Transfer Holder
Compatible with both Sandia and ALS XPS systems



Low-energy ion scattering (LEIS):
Directly detect H, surface conc. of other elements (first monolayer only)

Recrystallized NaAlH₄-Presence of Oxide



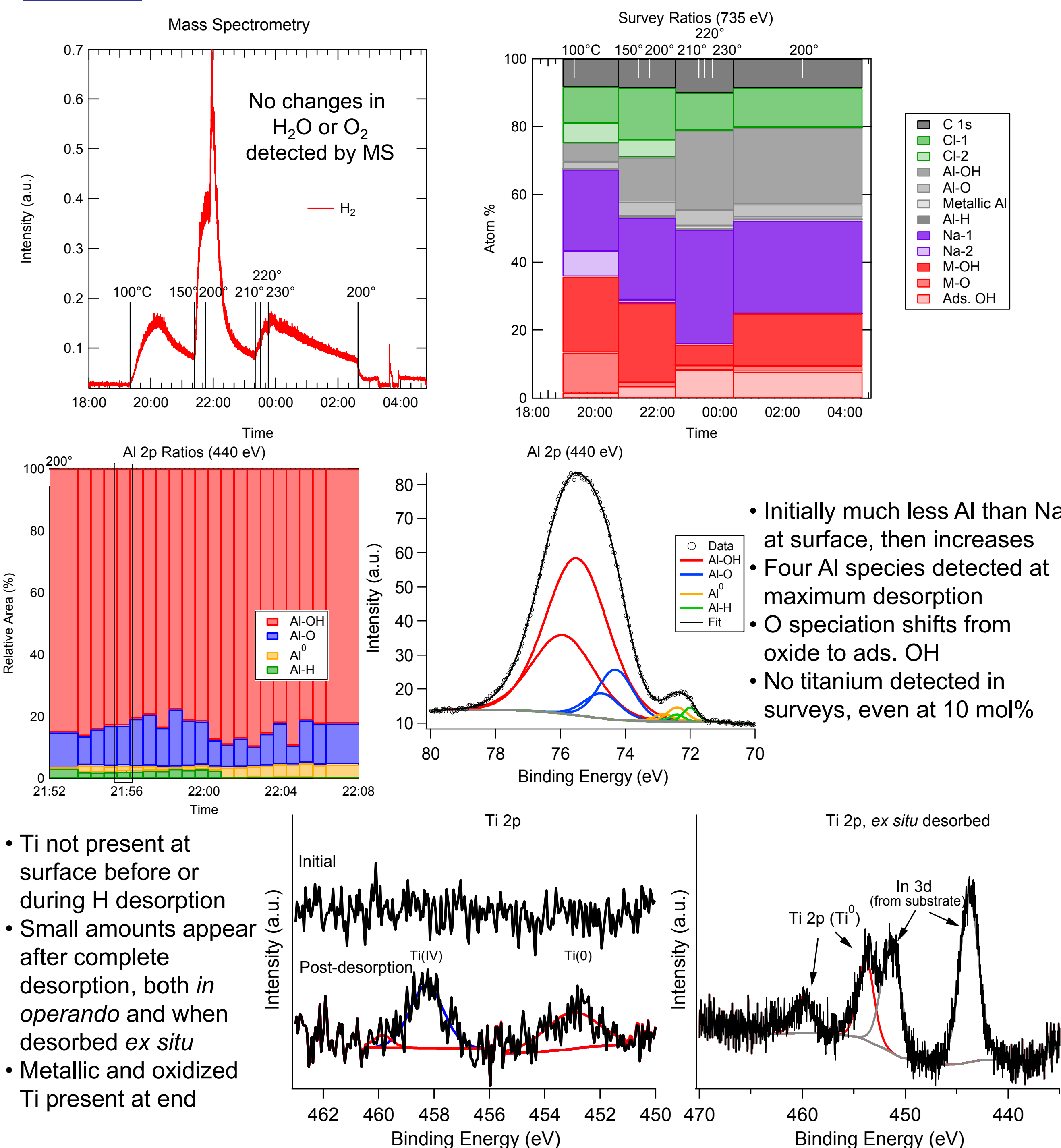
X-ray absorbance spectrum shows removal of oxidized impurities present in material as-received.

More surface-sensitive XPS found substantial oxygen content, in addition to Al-H,⁴ even on clean-transferred recrystallized material.

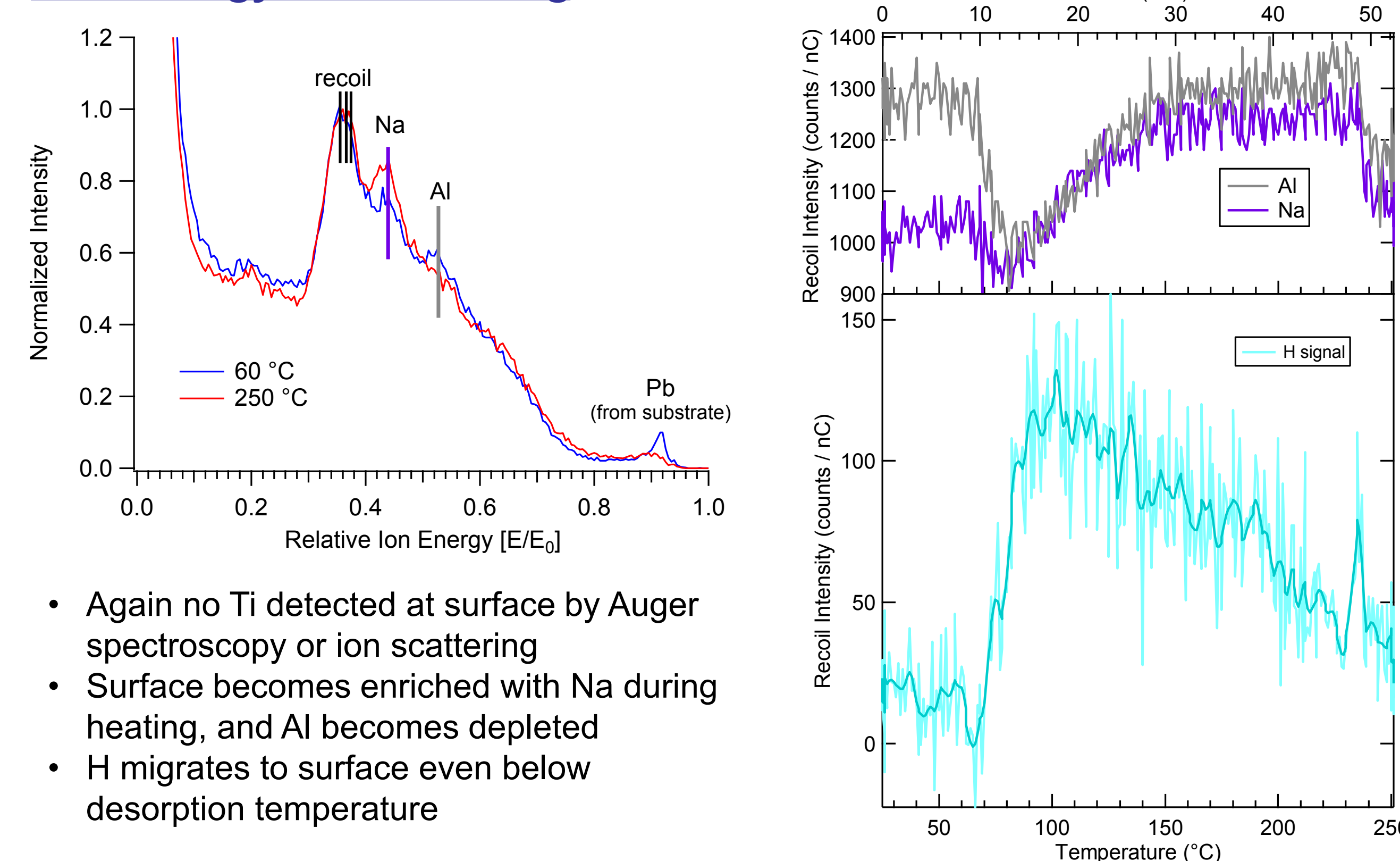
Surface oxidation not preventable; observation requires highly surface-sensitive techniques.

In Operando Surface Science of Hydrogen-Desorbing Ti-Doped NaAlH₄

AP-XPS



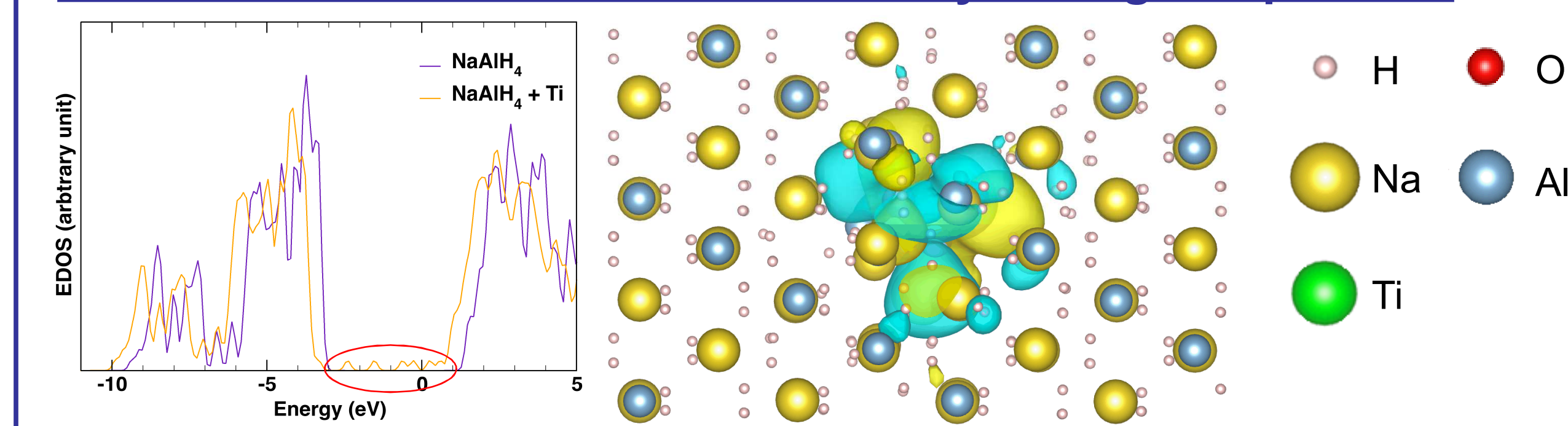
Low-Energy Ion Scattering



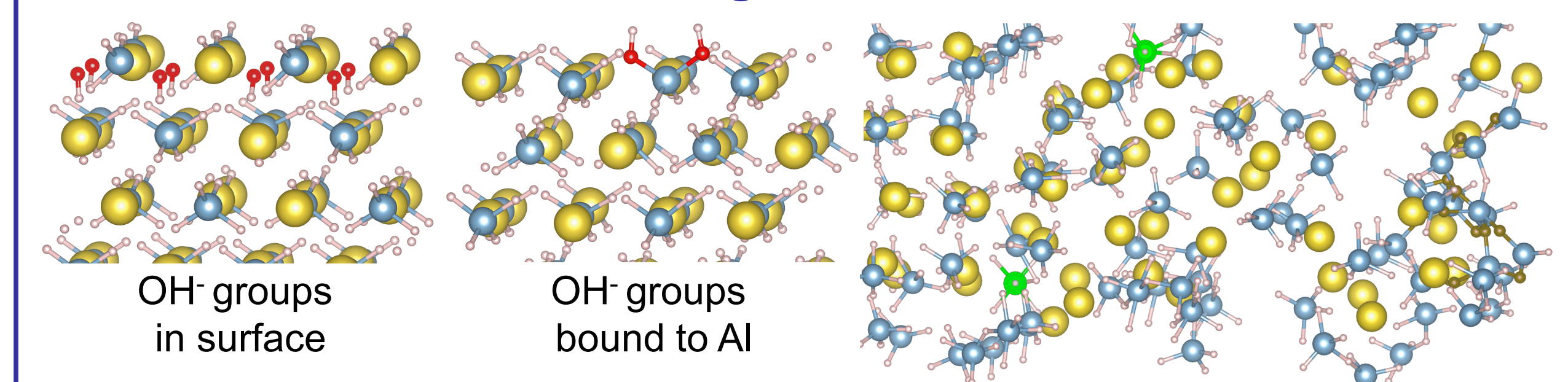
Absence of Ti at surface indicates no role in desorption, whereas dynamic O behavior suggests it is highly active in the process.

Computations of Ti-Doped NaAlH₄ with Oxygen

EDOS Shows Ti Enhances Conductivity through Gap States

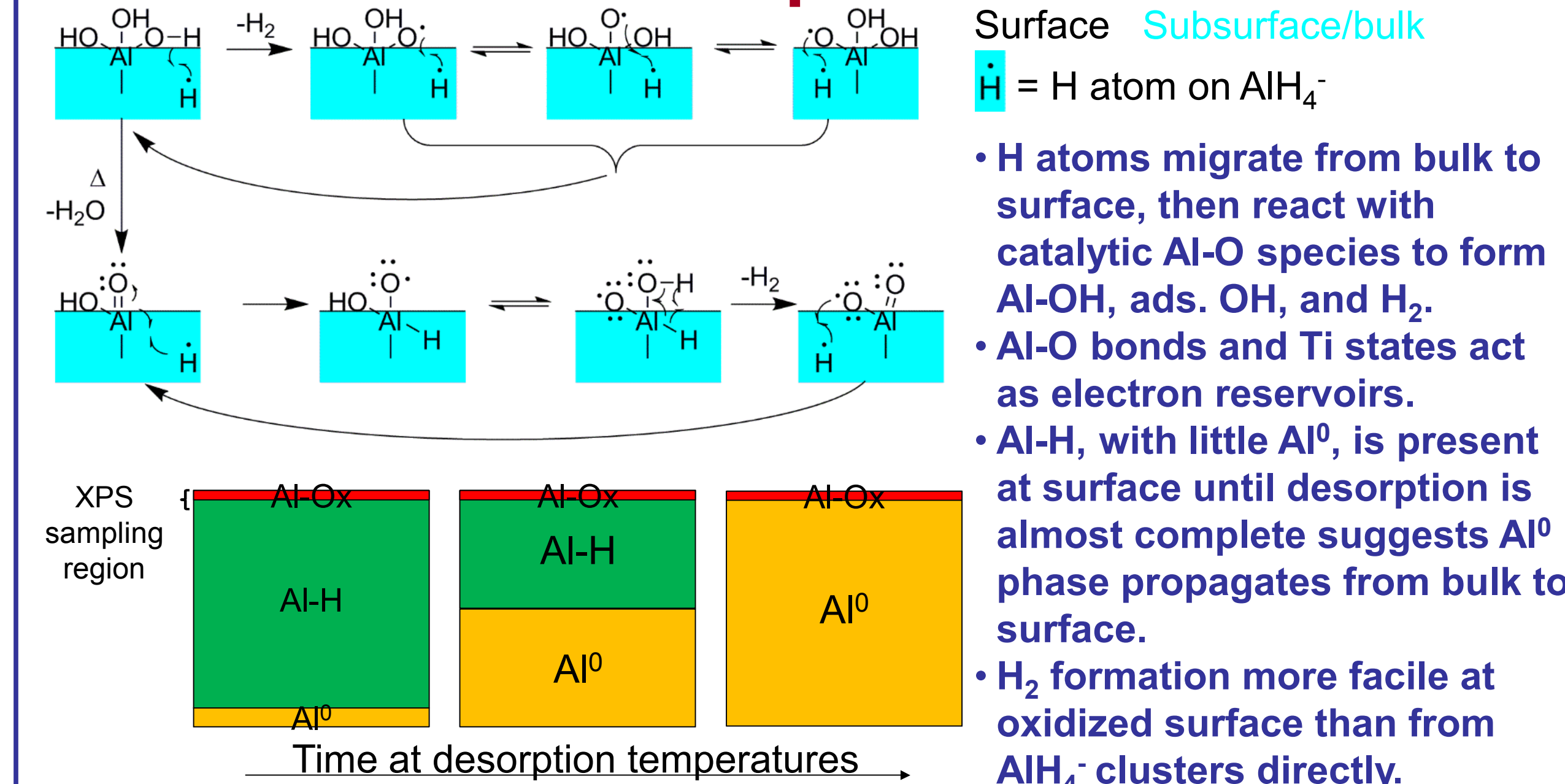


MD-Generated Surface Configurations for XPS Simulation



Delocalized states from Ti may aid in movement of electrons with hydrogen. Various O-containing species are stable at the NaAlH₄ (001) surface at 500 K.

Mechanism of Desorption at the Surface



Summary and Conclusions

- Realistic, cyclable TiCl₃-doped NaAlH₄ was prepared and analyzed by XPS and LEIS.
- The oxygen XPS spectrum was highly dynamic, shifting from more oxidized Al-O to more reduced Al-OH and adsorbed OH species as hydrogen desorbed.
- Formation of dehydrogenated phases propagates outward from the bulk toward the surface, with high Al-H concentrations remaining until near the end of desorption.
- No titanium was present at the surface, even at the high doping level of 10 mol%, until after desorption had completed. Ti thus cannot play a direct role in H₂ desorption.
- Computations indicate that oxidized Al species are stable on the surface and that titanium may have important electronic effects in the subsurface and bulk of NaAlH₄.

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